

Electronic and transport properties of topological material $Gd_xSb_{2-x}Te_3$

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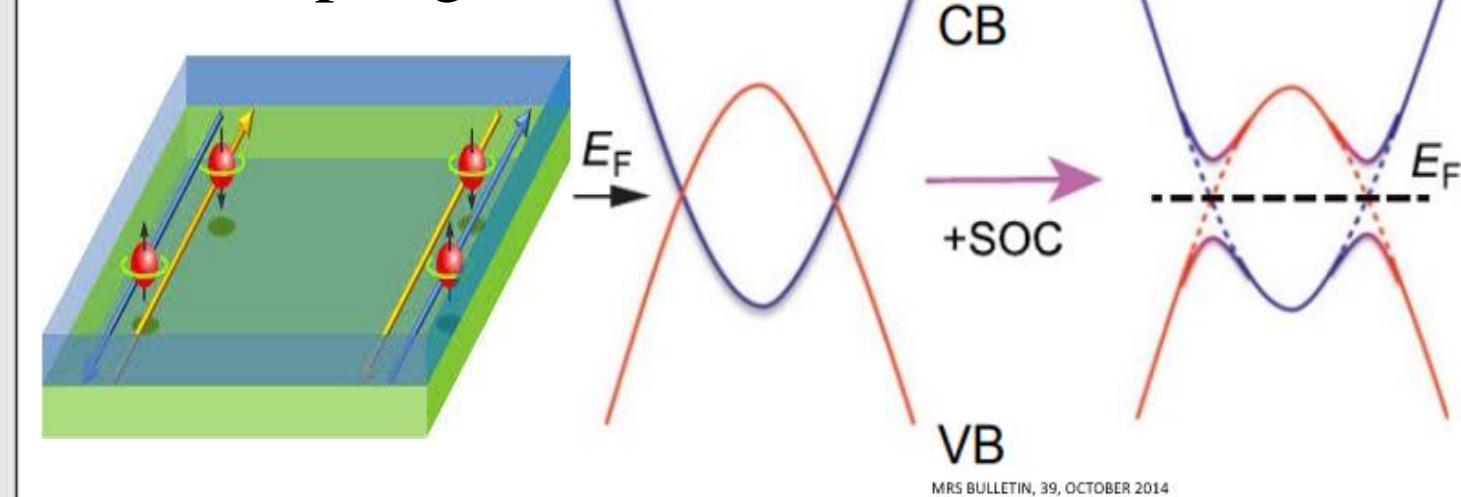
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Motivation

Topological Insulator (TI):

- ❖ Bulk band gap like an ordinary insulator but have protected conducting states on their edge or surface.
 - Due to spin-momentum locking, spin polarized electrons can move through surface.
 - Band inversion as a result of strong spin orbit coupling.

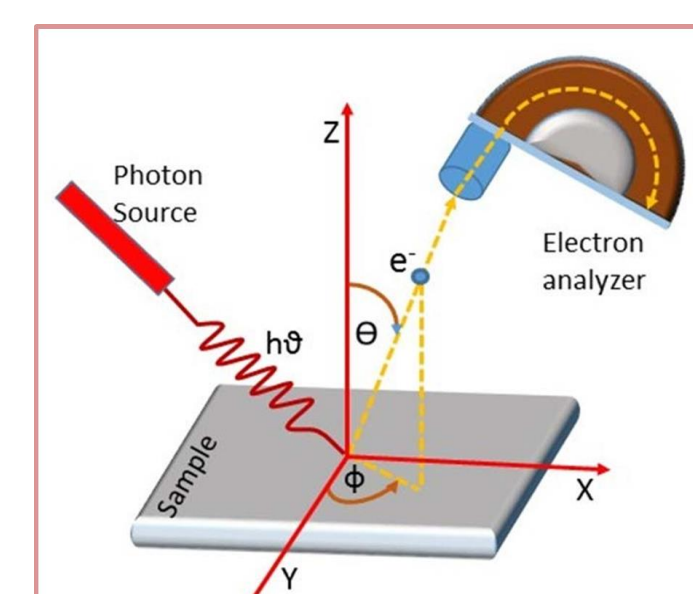


Gd doped TI ($\text{Gd}_x\text{Sb}_{2-x}\text{Te}_3$):

- ❖ Trigonal, space group: R3m [166]
- ❖ Parent Sb_2Te_3 is a strong TI.
- ❖ Energy band gap ~ 0.3 eV
- ❖ Crystal synthesis by flux method.
- ❖ Characterized by XRD and EDS.



PPMS



ARPES

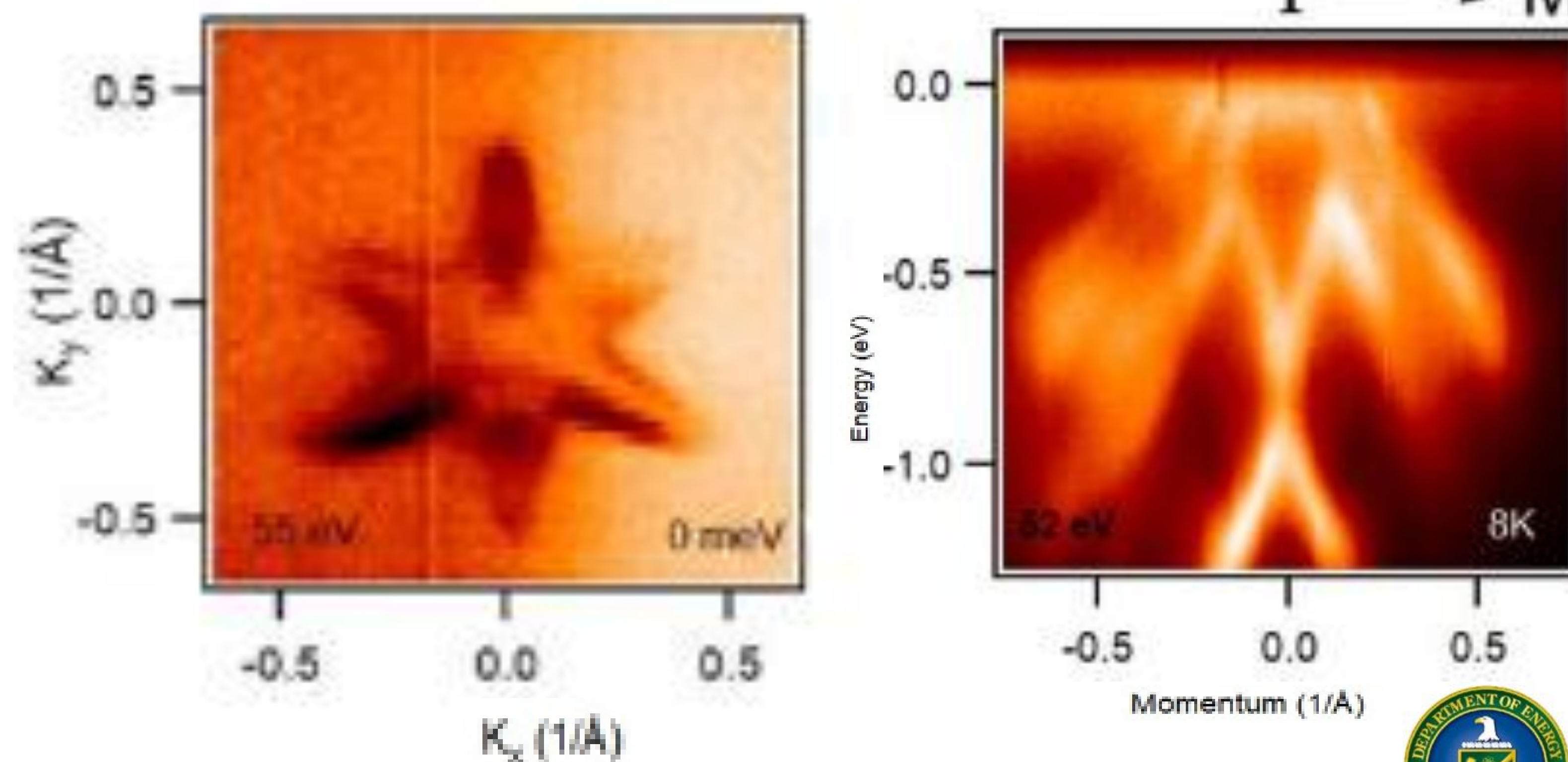
- ❖ Direct experimental technique based on the photoelectric effect.

$$E_{\text{kin}} = \hbar\omega - \Phi - |E_B|$$

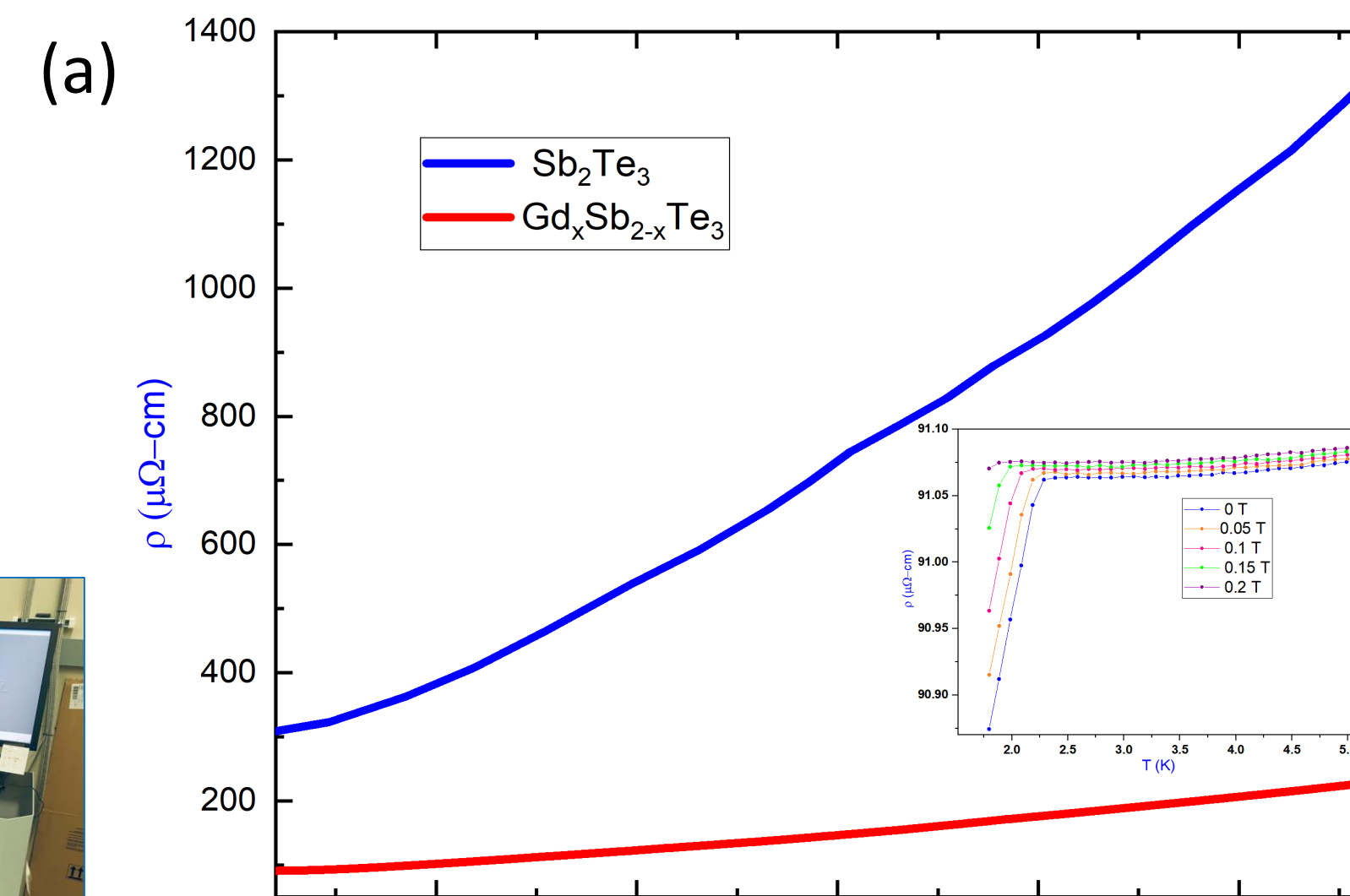
$$P_{||} = \hbar k_{||} = 2m E_{\text{kin}} \sin\theta$$

- ✓ Tuning Fermi energy by doping.
- ✓ Studies of electronic properties of this material.
- ✓ One of the best thermoelectric material.
- ✓ Archetypical TI (Sb_2Te_3)

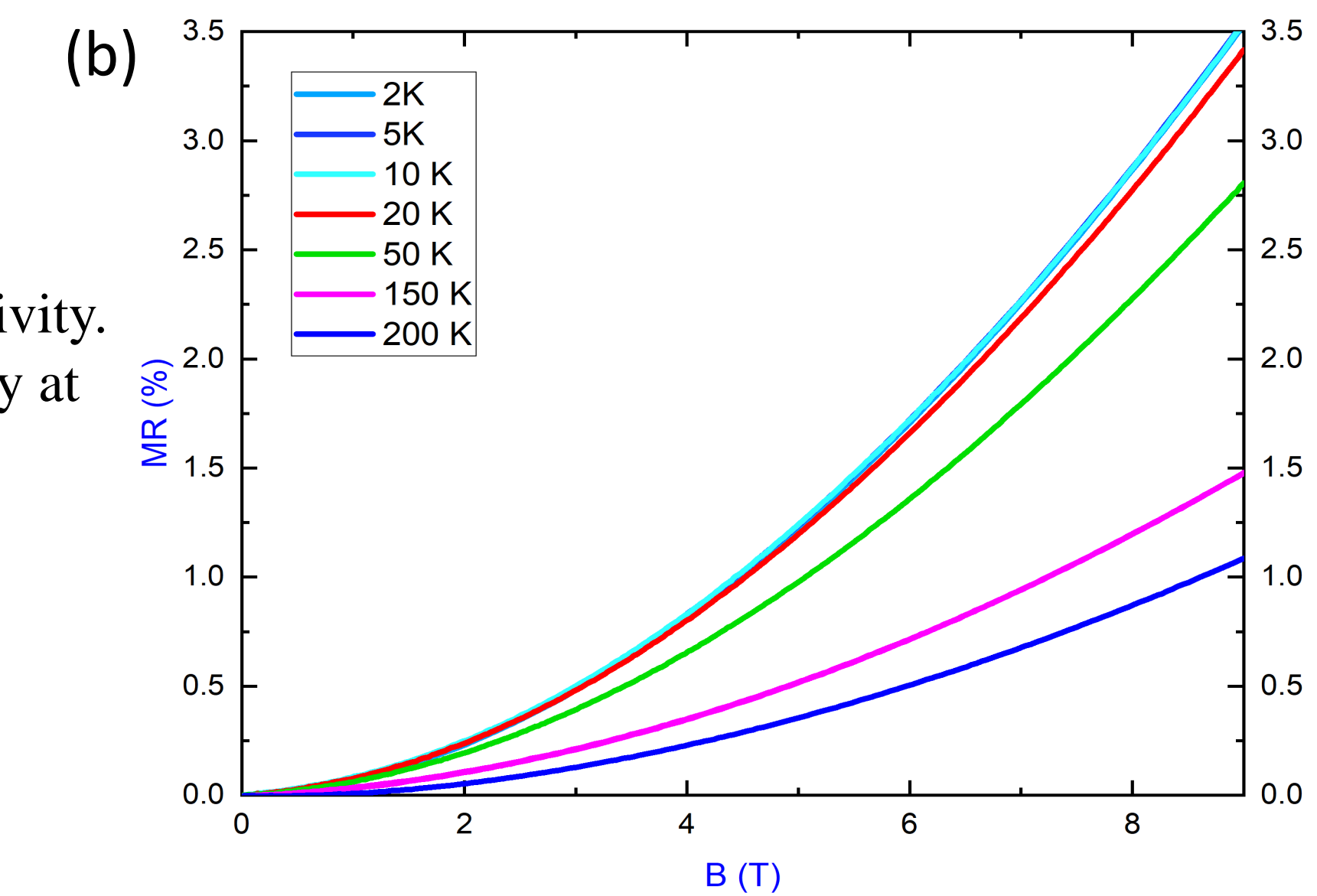
Fermi surface and Dispersion map of $\text{Gd}_x\text{Sb}_{2-x}\text{Te}_3$



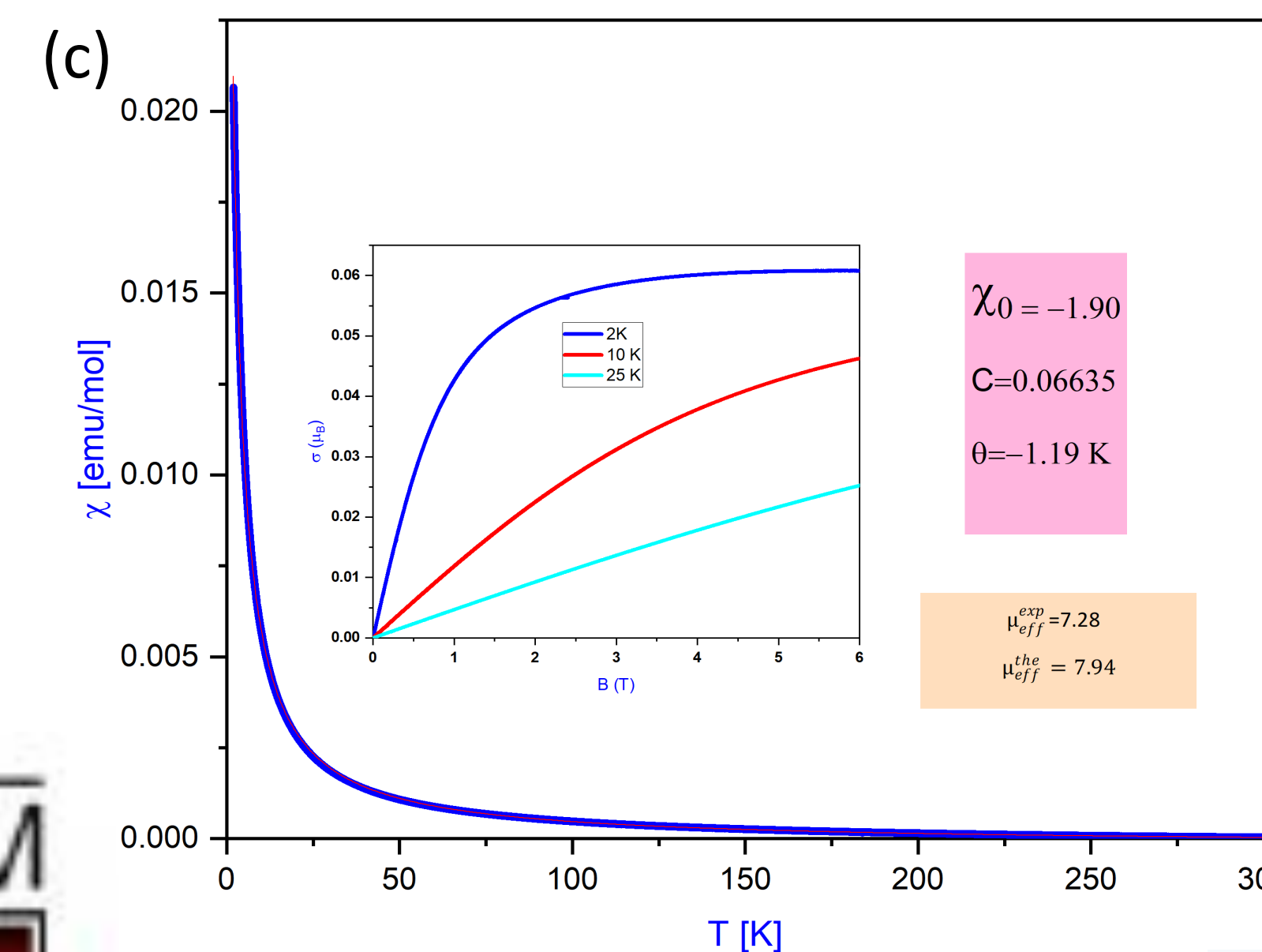
Transport and Magnetization properties of $\text{Gd}_x\text{Sb}_{2-x}\text{Te}_3$



- Metallic conductivity.
- Anomaly at 2.3 K??



- Relatively low MR $\sim 3.5\%$
- No saturation up to 9T.

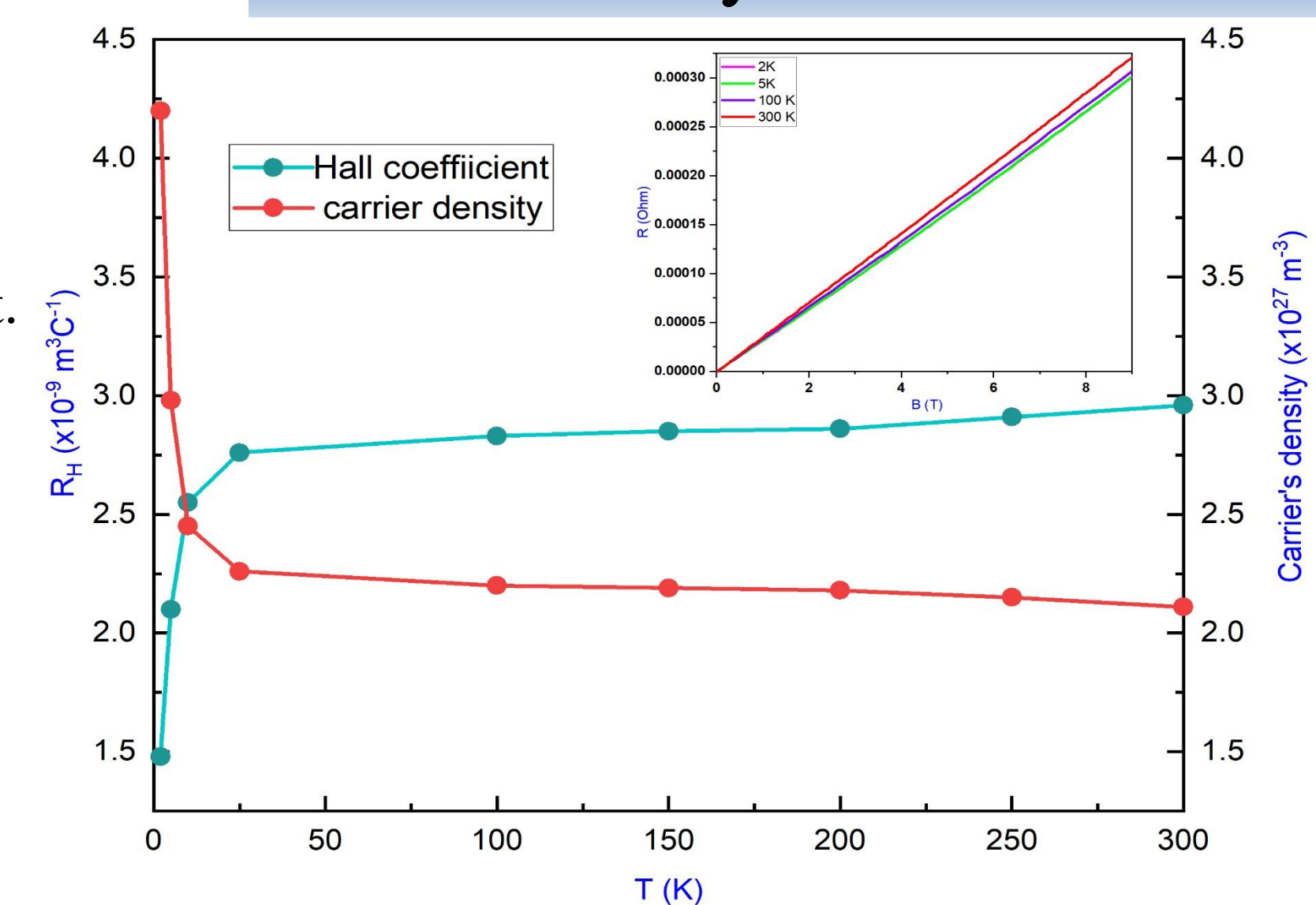


$$\mu_J^{\text{exp}} = 0.060 \mu_B$$

$$\mu_J^{\text{the}} = 2 \mu_B$$

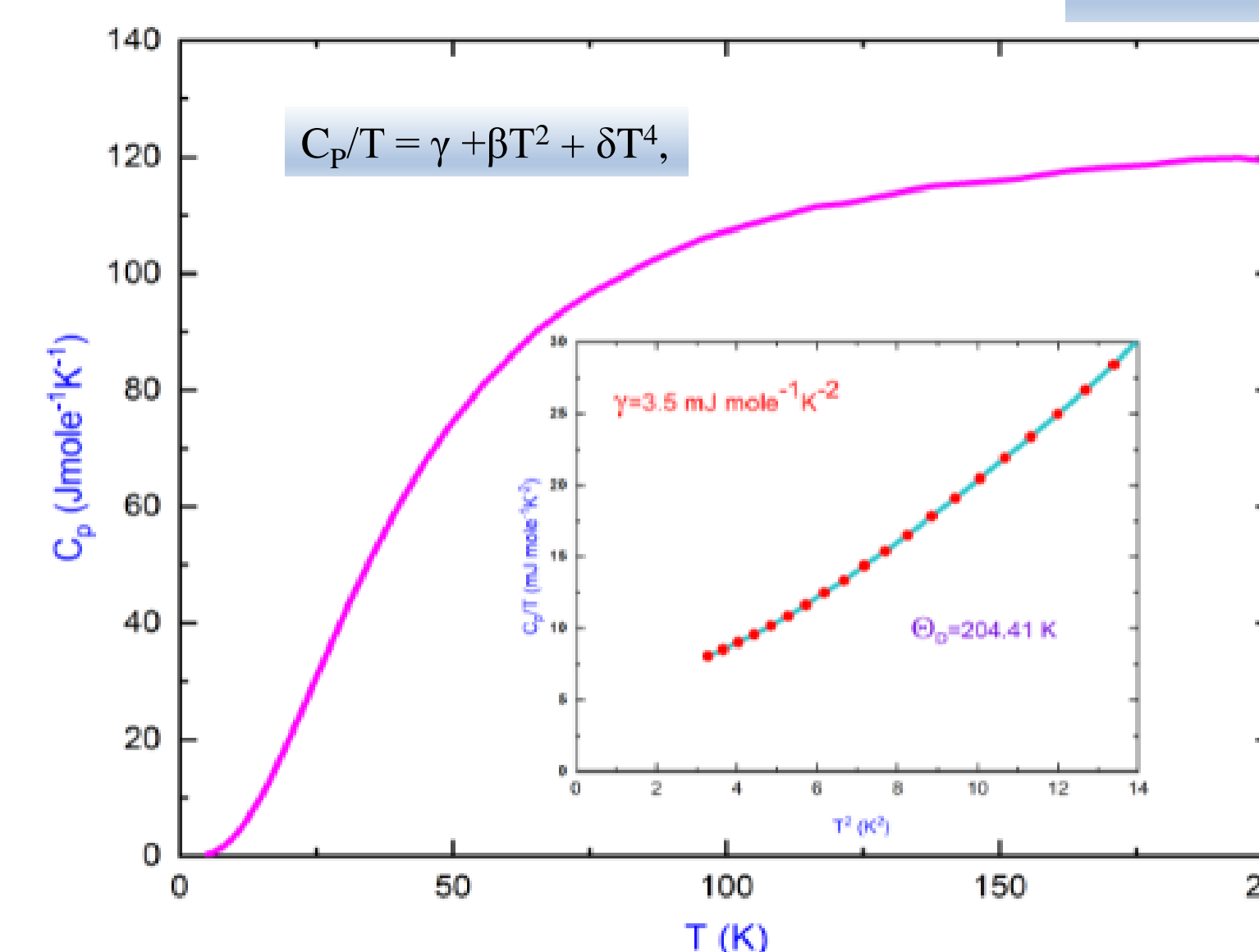
- Determine Gd content.
- Good agreement with EDS (1% Gd).

Hall resistivity and carrier concentration



- Positive (ordinary) Hall effect.
- Holes dominant.

Heat capacity measurement



Dulong Petit limit
 $3R \sim 125 \text{ J/mole}^{-1}\text{K}^{-1}$

- For parent Sb_2Te_3 , $\gamma = 0.7 \pm 0.7 \text{ mJ/mole}^{-1}\text{K}^{-2}$

Conclusion:

- ❖ Successfully synthesized $\text{Gd}_x\text{Sb}_{2-x}\text{Te}_3$.
- ❖ Significant influence of Gd on electronic properties.
- ❖ Magnetism: excellent probe of small Gd concentration in $\text{Gd}_x\text{Sb}_{2-x}\text{Te}_3$.

To be continued....

